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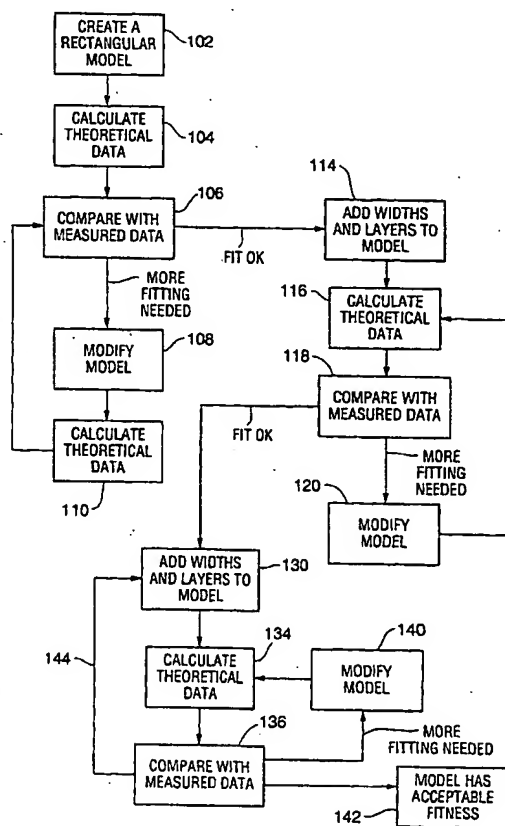
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(54) Title: REAL TIME ANALYSIS OF PERIODIC STRUCTURES ON SEMICONDUCTORS



(57) Abstract: A system for characterizing periodic structures formed on a sample on a real time basis is disclosed. Aspects of the system include a measurement module which generates output signals as a function of wavelength. The output signals are supplied to a processor for evaluation. The processor creates an initial theoretical model having a rectangular structure. The processor then calculates the theoretical optical response of that sample to broad band radiation. The calculated optical response is compared to normalized measured values at each of a plurality of wavelengths. Based on the comparison, the model configuration is modified to be closer to the actual measured structure. The processor recalculates the optical response of the modified model and compares the result to the normalized data. This process is repeated in an iterative manner until a best fit rectangular shape is achieved. Thereafter, the complexity of the model is iteratively increased, by dividing the model into layers each having an associated width and height. The model is fit to the data in an iterative manner until a best fit model is obtained which is similar in structure to the periodic structure. In the preferred embodiment, the processor consists of a plurality of parallel co-processors. The steps of calculating the optical response of the model is distributed to the processors as a function of wavelength so these calculations can be performed in parallel. An alternate embodiment using multiple angle of incidence measurements is also disclosed.

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